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(54) Title: NANOWIRE-BASED TRANSPARENT CONDUCTORS AND METHODS OF PATTERNING SAME

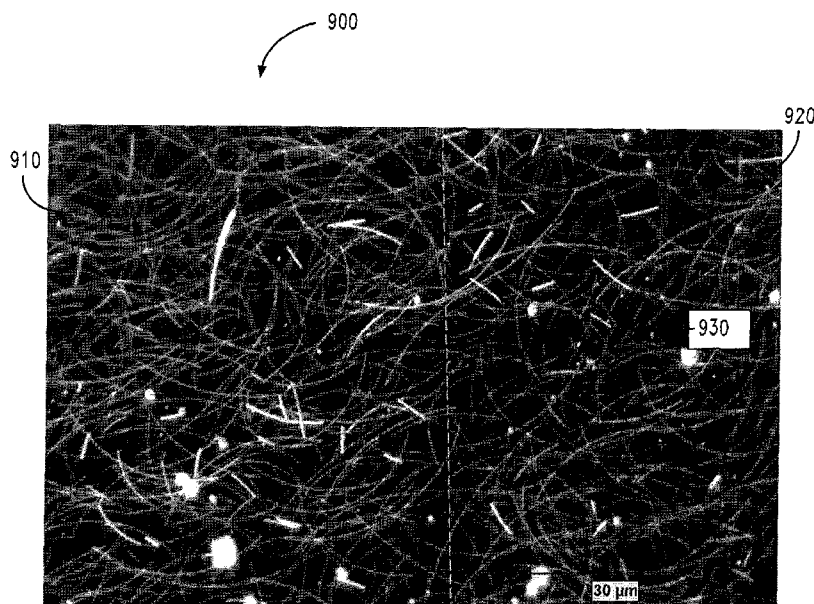


FIG. 43

(57) Abstract: Method of patterning nanowire-based transparent conductors are described. In particular, the methods are directed to partial etching that generates low-visibility or invisible patterns.



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